# Wide bandgap AlGaN semiconductors: doping and polarity

L. Spasevski<sup>1\*</sup>, P. R. Edwards<sup>1</sup>, G. Kusch<sup>1</sup>, R. W. Martin<sup>1</sup>, P. Pampili<sup>2</sup>, V. Z. Zubialevich<sup>2</sup>, P. J. Parbrook<sup>2</sup>, D. V. Dinh<sup>2,3</sup>

<sup>1</sup>Department of Physics, SUPA, University of Strathclyde, Glasgow, United Kingdom <sup>2</sup>Tyndall National Institute, University College Cork, Cork, Ireland <sup>3</sup>Department of Electronic and Electrical Engineering, University of Sheffield, Sheffield, UK \* lucia.spasevski@strath.ac.uk





## Introduction and motivation

- The AlGaN alloys are attractive material for optoelectronic devices, such as UV light emitting diodes (LEDs) and laser diodes (LDs) because of their direct and tunable wide band gap.
- Their employment requires certain crystal quality (sample morphology), defect density and doping concentration.
- Semipolar material has reduced polarisation fields along semipolar direction which results in an increase in radiative recombination probability
- N-type doping of AlGaN films with Si is difficult to achieve due to an increase in donor activation energy with an increase in AIN% content and the compensation of this donor by acceptor type defects such as oxygen, carbon and cation vacancies<sup>1,2,3</sup>
- Different scanning electron microscope techniques were employed to

## **Sample details**

• Grown by Metalorganic Chemical Vapour Deposition (MOVCD) in Tyndall Institute. 800-1100 nm thick Si-doped AlGaN layers, with reportedly 60 and 85 AlN% were grown on sapphire substrates (semi polar (11-22) or (0001) polar) orientation, covered with undoped AIN templates. The samples were grown with different  $Si_2H_6$  /group III ratios (0 to 3.35 x 10<sup>-4</sup>) and V/III ratios (23-600).

## **Cathodoluminescence (CL) spectroscopy**

High-Resolution CL Hyperspectral Imaging



investigate the doping, and the impact of the crystal orientation

• Precursors: TMGa, TMAI, NH<sub>3</sub>, Si<sub>2</sub>H<sub>6</sub>.

#### P. R. Edwards et al., Microsc. Microanal. 18, 1212 (2012)

Cathodoluminescence (CL) describes the emission of light from a material when it is excited by high energy electrons, for example originating from microscope beam. It is used to investigate luminescence properties of samples features and defects. While scanning the electron beam across the sample the entire room temperature CL spectrum is collected at each pixel thereby providing the multidimensional (hyperspectral) data set. Spatial resolution of the CL will depend on electron beam size, the size of the generation volume and upon the minority-carrier diffusion length.

## **CL** imaging

Centre energy map of NBE (near band edge) emission peak





• Lower energy emission at the edges of the hexagonal features. The differences in the CL maps are caused by lower incorporation of Al atoms at the edges. The difference is more pronounced for lower AIN content samples.<sup>5</sup>

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## **WDX** measurement

• In the EPMA technique elements can be identified according to their characteristic X-ray emission.

• Quantitative analysis



• RT-CL and WDX (Wavelength-dispersive X-ray spectroscopy) the experimental observed impurity-related data for complexes. Semi-polar and polar samples show the same trends for their emission, because of their similar nature

at the edges. They can be formed by spiral growth around screw or mixed type dislocations.<sup>5</sup> Semi-polar surface was much flatter with no hexagons.

### Summary

• In order to improve the IQE of UV LEDs it is crucial to reduce the density of point defects and dislocations in these alloys. 3D structures seen on polar samples cause surface roughening and the compositional variation at the edges. Effects of Si doping are not fully understood yet, but it seems that Si doping has little impact on the occurrence of surface features in the investigated sample series. CL spectra of the samples, confirmed the existence of impurity related complex associated with Si doping. The samples surface quality was improved by growth in semi-polar direction. NBE (near band edge) peaks were visible in all samples, and their emission was shifting according to AIN content.

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is performed by comparing the intensities measured for all the elements in the sample against standards of known composition. • The elemental composition is calculated after applying matrix corrections for atomic number, absorption and fluorescence effects (ZAF).